Claim 27 (previously presented): A photolithographic method, comprising:

providing a reticle comprising a plurality of patterned windows;

providing a photosensitive material;

a first exposure of the photosensitive material to a first light patterned with the reticle; the first exposure forming a first set of exposure patterns in the photosensitive material from the first light passing through the patterned windows;

a second exposure of the photosensitive material to a second light patterned with the reticle; the second exposure forming a second set of exposure patterns in the photosensitive material from the second light passing through the patterned windows;

displacing the reticle relative to the photosensitive material between the first and second exposures so that the first set of exposure patterns are interspersed within the second set of exposure patterns; and

wherein no portion of the photosensitive material is exposed to both the first light in the first exposure and the second light in the second exposure.

Claim 28 (previously presented): The method of claim 27 wherein the displacement of the reticle relative to the photosensitive material comprises movement of the reticle while the photosensitive material is held stationary.

Claim 29 (previously presented): The method of claim 27 wherein the displacement of the reticle relative to the photosensitive material comprises movement of the photosensitive material while the reticle is held stationary.

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Claim 30 (previously presented): The method of claim 27 wherein the displacement of the reticle relative to the photosensitive material comprises movement of both the photosensitive material and the reticle relative to one another.

Claim 31 (previously presented): The method of claim 27 wherein the first light has a different wavelength than the second light.

Claim 32 (previously presented): The method of claim 27 wherein the first light has the same wavelength as the second light.

Claim 33 (previously presented): A photolithographic method, comprising:

providing a reticle comprising a plurality of patterned windows corresponding to circuit device structures;

providing a photosensitive material;

a first exposure of the photosensitive material to a first light patterned with the reticle; the first exposure forming a first set of circuit device structure patterns in the photosensitive material from the first light passing through the patterned windows;

a second exposure of the photosensitive material to a second light patterned with the reticle; the second exposure forming a second set of circuit device structure patterns in the photosensitive material from the second light passing through the patterned windows;

displacing the reticle relative to the photosensitive material between the first and second exposures so that the first set of circuit device structure patterns are interspersed within the second set of circuit device structure patterns; and

wherein there is a two-to-one correspondence of circuit device structure patterns in the photosensitive material to patterned windows in the reticle after the first and second exposures.

Claim 34 (previously presented): The method of claim 33 wherein the displacement of the reticle relative to the photosensitive material comprises movement of the reticle while the photosensitive material is held stationary.

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Claim 35 (previously presented): The method of claim 33 wherein the displacement of the reticle relative to the photosensitive material comprises movement of the photosensitive material while the reticle is held stationary.

Claim 36 (previously presented): The method of claim 33 wherein the displacement of the reticle relative to the photosensitive material comprises movement of both the photosensitive material and the reticle relative to one another.

Claim 37 (previously presented): The method of claim 33 wherein the first light has a different wavelength than the second light.

Claim 38 (previously presented): The method of claim 33 wherein the first light has the same wavelength as the second light.